

# Agenda

Date: Wednesday, March 12<sup>th</sup>, 2025 13:30 – 18:45 CET

Thursday, March 13<sup>th</sup>, 2025 09:00 – 14:00 CET

Place: TU Eindhoven, Netherlands

March 12 <sup>th</sup> , 2025		
Olga Ohletz GenISys	Welcome & Introduction	13:30
Wilbert Rooijakkers TUE Nanolab	Introduction to the NanoLabTU/e	13:40
<b>Keynote</b> Regina Luttge TUE	<b>Lithography-enabled microfluidic chip technology</b>	13:55
Jochen Zimmer Nanoscribe	Aligned 2-Photon Lithography A2PL® for photonic integrated circuits	14:40
	Coffee Break & Cleanroom Window Tours	15:05
Koen Vanmol VU Brussel	2PP-based laser direct writing of interfacing microoptical components for short-range optical interconnects	16:40
Sven Bauerdick GenISys	Advanced SEM Metrology with ProSEM and InSPEC	17:05
	Process Workshop, Discussion and Snacks @ Bar Zwarte Doos	17:30
	End of Day 1	18:45
March 13 <sup>th</sup> , 2025		
Olga Ohletz GenISys	Welcome & Introduction	09:00
<b>Keynote</b> Kevin Williams TUE	<b>Frontiers in lithography with photonic integration</b>	09:05
Giulia Malvicini Paul Scherrer Institute PSI	3D Grayscale Fabrication in Thick Resists: Reducing Surface Roughness for Reflective X-Ray Focusing Optics	09:50
Nils Weimann University Duisburg-Essen	Electron Beam Lithography Processes for Terahertz and Millimeter-Wave Electronic Devices	10:15
	Coffee Break & Discussion	10:40
Kai Keller Notion	Additive Processes in Semicon Manufacturing: The Potential of Inkjet Technology	11:20
Peng Tian Paul Scherrer Institute PSI	The Transitioning of 3D Microfabrication of Microfluidic Biosensors: From E-Beam to Laser-Beam Grayscale Lithography	11:45
Anja Voigt micro resist technology	Innovative photoresists & photopolymers enabling advanced manufacture of photonic and micro-optical applications	12:10
Timo Oberbiermann Heidelberg Instruments Mikrotechnik	Grayscale exposure challenges using direct-write laser exposure on ultra-thick photosensitive positive resist	12:35
	Coffee & Discussion	13:00
	Closing of Day 2	14:00